

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) ~~A projection-An exposure apparatus that supplies liquid in a space between a projection optical system and a substrate and transfers a pattern on said substrate via said projection optical system and said liquid, said apparatus comprising:~~

~~a substrate table on which a substrate is mounted that can be moved that is movable while holding said a substrate;~~

~~an optical member that forms a pattern onto the substrate on the substrate table through a liquid which partially fills a space between the optical member and the substrate; and~~

~~a correction unitcorrecting device that corrects a positional deviation occurring in at least one of saidthe substrate on the substrate table and saidthe substrate table, the positional deviation being caused by due to supply of saidthe liquid-liquid.~~

2. (Currently Amended) The projection exposure apparatus of Claim 1, ~~saidthe~~ apparatus further comprising:

~~a position measuring systemdevice that measures obtains positional information of saidthe substrate table, wherein~~

~~saidthe correction unitcorrecting device corrects a positional deviation occurring in at least one of saidthe substrate and saidthe substrate table due to supply of said liquid according to the position of saidthe substrate table measured which is obtained by saidthe position measuring systemdevice.~~

3. (Currently Amended) The projection exposure apparatus of ~~Claim 2-Claims 2,~~ wherein

said~~the~~ correction unit~~the~~ correcting device corrects an error in said~~the~~ positional information in at least one of said~~the~~ substrate and said~~the~~ substrate table measured obtained directly or indirectly by said~~the~~ position measuring system~~device~~, which occurs due to supply of said~~the~~ liquid.

4. (Currently Amended) The projection exposure apparatus of Claim 1~~Claim 1~~, wherein

said~~the~~ correction unit~~the~~ correcting device corrects a positional deviation that occurs by a change in the shape of said~~the~~ substrate table.

5. (Currently Amended) The projection exposure apparatus of Claim 1~~Claim 1~~, wherein

said~~the~~ substrate table has a fiducial member used for position setting, and said~~the~~ correction unit~~the~~ correcting device corrects a positional deviation between said~~the~~ fiducial member and said~~the~~ substrate.

6. (Currently Amended) The projection exposure apparatus of Claim 1~~Claim 1~~, wherein

said~~the~~ correction unit~~the~~ correcting device corrects the distance between said  
projection optical system~~the~~ optical member and said~~the~~ substrate in an optical axis direction of saidprojection optical system~~the~~ optical member.

7. (Currently Amended) The projection exposure apparatus of Claim 1~~Claim 1~~, wherein

said~~correction unit~~the correcting device corrects said~~the~~ positional deviation according to a physical quantity related to said~~the~~ liquid.

8. (Currently Amended) The projection exposure apparatus of Claim 7~~Claim 7~~, wherein

saidthe physical quantity related to saidthe liquid includes at least one of pressure of saidthe liquid and surface tension of saidthe liquid.

9. (Currently Amended) The projection-exposure apparatus of Claim 1Claim 1, wherein

saidthe correction unitcorrecting device corrects a positional deviation that occurs by vibration of saidthe substrate table.

10. (Currently Amended) The projection-exposure apparatus of Claim 1, saidthe apparatus further comprising:

a mask stage on which a mask having saidthe pattern formed is mounted that can be moved holding saidthe mask; and

saidthe correction unitcorrecting device corrects saidthe positional deviation by changing a thrust given to at least one of saidthe substrate table and saidthe mask stage.

11. (Currently Amended) The projection-exposure apparatus of Claim 10Claim 10, wherein

saidthe correction unitcorrecting device comprises a controller that changes saidthe thrust by feedforward control.

12. (Currently Amended) The projection-exposure apparatus of Claim 1Claim 1, wherein

saidthe correction unitcorrecting device corrects saidthe positional deviation based on position measuring obtaining results of a transferred image of saidthe pattern transferred on saidthe substrate.

13. (Currently Amended) The projection-exposure apparatus of Claim 1Claim 1, wherein

saidcorrection unitthe correcting device corrects saidthe positional deviation based on simulation results.

14. (Currently Amended) A stage unit device that has a substrate table which movably holds a substrate whose surface is supplied with a liquid, said unit the device comprising:

a position measuring unit device that measures obtains positional information of said the substrate table; and

a correction unit correcting device that corrects a positional deviation occurring in at least one of said the substrate on the substrate table and said the substrate table, the positional deviation being caused by due to supply of said the liquid liquid, wherein an immersion area is defined by an area where the liquid is located, and the immersion area is smaller than the surface of the substrate on the substrate table.

15. (Currently Amended) The stage unit device of Claim 14-Claim 14, wherein said the correction unit correcting device corrects a positional deviation that occurs by a change in the shape of said the substrate table.

16. (Currently Amended) The stage unit device of Claim 14-Claim 14, wherein said the substrate table has a fiducial member used for position setting, and said the correction unit correcting device corrects positional deviation between said the fiducial member and said the substrate.

17. (Currently Amended) An exposure method in which liquid is supplied to a space between a projection optical system and a substrate held on a substrate table and a pattern is transferred onto said substrate via said projection optical system and said liquid which forms a pattern onto a substrate held by a substrate table, said the method comprising:

a detection process in which detecting a change occurring that occurs in at least one of said the substrate and said the substrate table due to caused by supply of said a liquid is detected; and

~~a transfer process in which said pattern is transferred onto said substrate based on results of said detection forming the pattern onto the substrate based on results of the detecting a change, by irradiating a radiation beam through an optical member and the liquid which partially fills a space between the optical member and the substrate on the substrate table.~~

18. (Currently Amended) The exposure method of ~~Claim 17~~ Claim 17, wherein ~~in said transfer process, said transfer~~ the forming the pattern is performed with at least one of a positional deviation that occurs by a change in the shape of ~~said~~ the substrate table and the distance between ~~said projection optical system~~ the optical member and ~~said~~ the substrate in an optical axis direction of ~~said projection optical system~~ the optical member corrected.

19. (Currently Amended) The exposure method of ~~Claim 17~~ Claim 17, wherein ~~in said detection process, the detecting a change detects~~ a change according to a physical quantity related to ~~said~~ the liquid is detected, and ~~in said transfer process, said transfer~~ the forming the pattern is performed with ~~said~~ the change according to ~~said~~ the physical quantity related to ~~said~~ the liquid corrected.

20. (Currently Amended) The exposure method of ~~Claim 19~~ Claim 19, wherein ~~said~~ the physical quantity related to ~~said~~ the liquid includes at least one of pressure of ~~said~~ the liquid and surface tension of ~~said~~ the liquid.

21. (Currently Amended) The exposure method of ~~Claim 17~~ Claim 17, wherein ~~in said transfer process, said transfer~~ the forming the pattern is performed with a positional deviation that occurs by vibration of ~~said~~ the substrate table corrected.

22. (Currently Amended) The exposure method of ~~Claim 17~~ Claim 17, wherein

~~in said transfer process, said transfer~~ the forming the pattern is performed with ~~said~~the change corrected by changing a thrust given to at least one of ~~said~~the substrate table and a mask stage on which a mask where ~~said~~the pattern is formed is mounted.

23. (Currently Amended) The exposure method of Claim 22, wherein the change of ~~said~~the thrust is performed by feedforward control.

24. (Currently Amended) The exposure method of Claim 17, wherein ~~said~~the change is corrected based on position measuring obtaining results of a transferred image of ~~said~~the pattern transferred on ~~said~~the substrate.

25. (Currently Amended) The exposure method of Claim 17, wherein ~~said~~the change is corrected based on simulation results.

26. (Currently Amended) The projection exposure apparatus of Claim 1, wherein

supply of ~~said~~the liquid in ~~said~~the space between ~~said~~the projection optical system ~~the~~ optical member and ~~said~~the substrate is performed by a liquid supply unit device, and

~~said~~the liquid supply unit device supplies the liquid to a part of ~~said~~the substrate.

27. (Currently Amended) The projection exposure apparatus of Claim 1, wherein

~~said~~the substrate table has a holding member that holds ~~said~~the substrate and plate members arranged in the periphery of ~~said~~the holding member.

28. (Currently Amended) The projection exposure apparatus of Claim 2, wherein

~~said~~the position measuring system device measures obtains positional information of ~~said~~the substrate table without involving ~~said~~the liquid.

29. (Currently Amended) The stage unit device of Claim 14Claim 14, wherein supply of saidthe liquid to saidthe substrate is performed by saida liquid supply unitdevice, and

saidthe liquid supply unit device supplies liquid to a part of saidthe substrate.

30. (Currently Amended) The stage unit device of Claim 14Claim 14, wherein saidthe substrate table has a holding member that holds saidthe substrate and plate members arranged in the periphery of saidthe holding member.

31. (Currently Amended) The stage unit device of Claim 14Claim 14, wherein saidthe position measuring systemdevice measuresobtains positional information of saidthe substrate table without involving saidthe liquid.

32. (Currently Amended) The exposure method of Claim 17Claim 17, wherein saidthe liquid is supplied to a part of saidthe substrate.

33. (Currently Amended) The exposure method of Claim 17Claim 17, wherein on saidthe substrate table, plate members are arranged in the periphery of a holding member that holds saidthe substrate.

34. (New) The exposure apparatus of Claim 1, wherein an immersion area is defined by an area where the liquid is located and the immersion area is smaller than a surface of the substrate held by the substrate table.

35. (New) The exposure apparatus of Claim 34, wherein the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.

36. (New) The stage device of Claim 14, wherein the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.

37. (New) The exposure apparatus of Claim 17, wherein

an immersion area is defined by an area where the liquid is located and the immersion area is smaller than a surface of the substrate held by the substrate table.

38. (New) The exposure method of Claim 37, wherein  
the immersion area is movable on the surface of the substrate in accordance with the movement of the substrate table.

39. (New) A stage device comprising:  
a table that is movable while holding an object whose surface is supplied with a liquid, wherein an immersion area where the liquid is located is smaller than the surface of the object held by the table;  
a position measuring device that obtains positional information of the table; and

a control device that obtains a positional deviation related to the positional information of the table obtained by the position measuring device, the positional deviation being caused by supply of the liquid.

40. (New) The stage device of Claim 39, wherein  
the control device obtains the positional deviation according to a property of the liquid.

41. (New) The stage device of Claim 40, wherein  
the property includes at least one of pressure of the liquid, surface tension of the liquid, a flow of the liquid, and a contact angle of the liquid.

42. (New) The stage device of Claim 40, further comprising:  
a memory that stores a relation between the property and the positional deviation.

43. (New) The stage device of Claim 39, wherein  
the table has a fiducial member used for position setting of the table, and

the control device obtains a positional deviation between the fiducial member and the object held by the table.

44. (New) An exposure apparatus comprising:
  - a stage device according to Claim 39, wherein the object is a substrate; and
  - an optical member that forms a predetermined pattern on the substrate.